Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3279	438/706	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/27 11:32
L2	3	1 and (gas near protecting)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/27 11:33
S1	3091	photo near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S2	24887	photoresist near pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:36
S3	27744	S1 or S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S6	15166	i-line or KrF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:37
S7	1807	S3 and S4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S8	10744	ArF or UvU or EUF	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S9	128	S7 and S8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38

S10	411399	resist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:38
S11	. 66	S9 and S10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:51
S12	2	"4491628".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56
S13	1	10/719083	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 07:56
S14	336	("4491628").URPN.	USPAT	OR	ON	2005/08/25 08:43
S15	965	tri-level	USPAT	OR	ON	2005/08/25 08:43
S16	68113	photoresist	USPAT	OR	ON	2005/08/25 08:43
S17	21	S15 near S16	USPAT	OR	ON	2005/08/25 10:05
S18	454581	polymer	USPAT	OR	ON	2005/08/25 10:05
S19	365962	silicon	USPAT	OR	ON	2005/08/25 10:06
S20	191357	mask	USPAT	OR	ON	2005/08/25 10:06
S21	1	S18 near S19 near S20	USPAT	OR	ON	2005/08/25 10:09
S22	1	silicon near polymer near mask	USPAT	OR	ON	2005/08/25 10:09
S23	1	silicon near polymer near etch	USPAT	OR	ON	2005/08/25 10:09
S24	357	S18 near S20	USPAT	OR	ON	2005/08/25 10:14
S25	3334	i-line	USPAT	OR	ON	2005/08/25 10:14
S26	191357	mask	USPAT	OR	ON	2005/08/25 10:14
S27	2761	S25 and S26	USPAT	OR	ON	2005/08/25 10:15
S28	365962	silicon	USPAT	OR	ON	2005/08/25 10:15
S29	2131	S27 and S28	USPAT	OR	ON	2005/08/25 10:15
S30	186985	poly	USPAT	OR	ON	2005/08/25 10:15
S31	692	S29 and S30	USPAT	OR	ON	2005/08/25 10:53
S32	1874	gas near absorbing	USPAT	OR	ON	2005/08/25 10:54
S33	766	oxygen near absorbing	USPAT	OR	ON	2005/08/25 10:54
S34	200051	resist	USPAT	OR	ON	2005/08/25 10:54
S35	96988	spin	USPAT	OR	ON	2005/08/25 10:54

S36	14776	bake	USPAT	OR	ON	2005/08/25 10:54
S39	151804	water adj soluble	USPAT	OR	ON	2005/08/25 10:56
S40	454581	polymer	USPAT	OR	ON	2005/08/25 10:56
S41	20443	S39 near S40	USPAT	OR	ON	2005/08/25 10:56
S42	3403	S35 and S36	USPAT	OR	ON	2005/08/25 10:56
S43	36	S41 and S42	USPAT	OR	ON	2005/08/25 10:57
S44	30	S43 and S34	USPAT	OR	ON	2005/08/25 11:04
S46	2594	S32 or S33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 10:57
S50	195	S34 and S46	USPAT	OR	ON	2005/08/25 11:05
S51	23	S50 and S39	USPAT	OR	ON	2005/08/25 11:14
S52	53	organic adj polysilane	USPAT	OR	ON	2005/08/25 11:14
S53	68113	photoresist	USPAT	OR	ON	2005/08/25 11:14
S54	8	S52 and S53	USPAT	OR	ON	2005/08/25 14:15
S55	0	organic adj polysilane adj photoresist	USPAT	OR	ON	2006/03/07 11:10
S56	0	organic adj polysilane adj resist	USPAT	OR	ON	2005/08/25 13:46
S57	0	organic adj polysilane near resist	USPAT	OR	ON	2005/08/25 13:46
S58	13	organic adj polysilane and resist	USPAT	OR	ON	2005/08/25 13:46
S61	1	10/712,446	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/25 14:16
S62	2	"5962191".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 08:09
S63	79	((polytmethyl adj methacrylate) or (polytmethyl adj acrylic adj acid) or (polytmethyl adj acrylate) or (polytmethyl adj acrylic adj acid) or (polytdimethyl adj acrylate) or (methyl adj acrylate) or (polytdimethyl adj acrylate) (polytdimethyl adj methyl adj methacrylate) or (polytmethyl adj polytvinyl adj pyrrolidone) or (polytdimethyl adj acrylate)) and PGMEA	USPAT	OR	ON	2006/09/01 18:46
S64	2491	S63 and AfF or VUV or EUV	USPAT	OR	ON	2006/03/07 11:14

S65	6	S63 and (AfF or VUV or EUV)	USPAT	OR	ON	2006/03/07 11:14
S66	2	"5,702,776".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S67	0	(silicon adj gas) near (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S68	0	(silicon adj gas) same (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/09/01 15:44
S69	0	(silicon adj gas) with (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:44
S70	18	(silicon adj gas) and (photo adj resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 15:45
S71	2	"20040266203"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 16:45
S72	2	"6861199".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/01 16:45
S73	0	((polytmethyl adj methacrylate) near (polyacrylic adj acid)) or ((polytmethyl adj acrylate) near (polyacrylic adj acid)) or ((polydimethyl adj acrylate) near (polymethyl adj acrylate)) or ((polytdimethyl adj acrylate) near (polytmethyl adj methacrylate)) or (polytvinyl adj pyrrolidone) or (polytdimethyl adj acrylate)	USPAT	OR	ON	2007/03/13 17:15

S74	0	((polytmethyl adj methacrylate) near (acrylic adj acid)) or ((polytmethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polytdimethyl adj acrylate) near (methyl adj methacrylate)) or (polytvinyl adj pyrrolidone) or (polytdimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:58		
S75	15034	((methyl adj methacrylate) near (acrylic adj acid)) or ((methyl adj acrylate) near (acrylic adj acid)) or ((dimethyl adj acrylate) near (methyl adj acrylate)) or ((dimethyl adj acrylate) near (methyl adj methacrylate)) or (vinyl adj pyrrolidone) or (dimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:57		
S76	23434	((polymethyl adj methacrylate) near (acrylic adj acid)) or ((polymethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polydimethyl adj acrylate) near (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:57		
S77	23434	((polymethyl adj methacrylate) near (acrylic adj acid)) or ((polymethyl adj acrylate) near (acrylic adj acid)) or ((polydimethyl adj acrylate) near (methyl adj acrylate)) or ((polydimethyl adj acrylate) near (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 19:01		
S78	23453	((polymethyl adj methacrylate) near (polyacrylic adj acid)) or ((polymethyl adj acrylate) near (polyacrylic adj acid)) or ((polydimethyl adj acrylate) near (polymethyl adj acrylate)) or ((polydimethyl adj acrylate) near (polymethyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 18:58		
S79	23564	S76 or S77 or S78	USPAT	OR	ON	2006/09/01 18:59		
S80	73628	photoresist	USPAT	OR	ON	2006/09/01 18:59		
S81	1	S79 near S80	USPAT	OR	ON	2006/09/01 19:02		
S82	0	S75 near S80	USPAT	OR	ON	2006/09/01 19:01		

S83	24222	((polymethyl adj methacrylate) with (acrylic adj acid)) or ((polymethyl adj acrylate) with (acrylic adj acid)) or ((polydimethyl adj acrylate) with (methyl adj acrylate)) or ((polydimethyl adj acrylate) with (methyl adj methacrylate)) or (polyvinyl adj pyrrolidone) or (polydimethyl adj acrylate)	USPAT	OR	ON	2006/09/01 19:25
S84	32	S83 with S80	USPAT	OR	ON	2006/09/01 19:16
S85	0	S84 and gas near absorbing	USPAT	OR	ON	2006/09/01 19:05
S86	0	S84 and (gas near absorbing)	USPAT	OR	ON	2006/09/01 19:05
S87	0	S83 with ("193" adj nm adj photo adj resist)	USPAT	OR	ON	2006/09/01 19:16
S88	1	("193" adj nm adj photo adj resist)	USPAT	OR	ON	2006/09/01 19:16
S89	4	"193" near (photo adj resist)	USPAT	OR	ON	2006/09/01 19:17
S90	133	"193" near (photoresist)	USPAT	OR	ON	2006/09/01 19:17
S91	135	S89 or S90	USPAT	OR	ON	2006/09/01 19:17
S92	0	S91 with S83	USPAT	OR	ON	2006/09/01 19:17
S93	2	S91 and S83	USPAT	OR	ON	2006/09/01 19:18
S94	647	S83 and S80	USPAT	OR	ON	2006/09/01 19:26
S95	0	S94 and (gas adj absorbing)	USPAT	OR	ON	2006/09/01 19:26
S96	387	S94 and (water adj soluble)	USPAT	OR	ON	2006/09/01 19:27
S97	150	S94 and (water adj soluble adj polymer)	USPAT	OR	ON	2006/09/01 19:27
S98	73	S97 and resist	USPAT	OR	ON	2006/09/01 19:27
S99	30	S98 and semiconductor	USPAT	OR	ON	2006/09/01 20:17
S10 0	1	"6692892".pn.	USPAT	OR	ON	2006/09/01 20:18
S10 1	2	"6,692,892".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/05 09:37
S10 5	2718	((polymethyl adj methacrylate) and (polyacrylic adj acid)) or ((polymethyl adj acrylate) and (polyacrylic adj acid))	USPAT	OR	ON	2007/03/13 17:17
S10 6	280	((polymethyl adj methacrylate) near (polyacrylic adj acid)) or ((polymethyl adj acrylate) near (polyacrylic adj acid))	USPAT	OR	ON	2007/03/14 10:46

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S10 9	280	((polymethyl adj methacrylate) near (polyacrylic adj acid)) or ((polymethyl adj acrylate) near (polyacrylic adj acid))	USPAT	OR	ON	2007/03/14 11:11
S11 0	15	S109 and photoresist	USPAT	OR	ON	2007/03/14 11:04
S11 1	0	S110 and (gas near protecting)	USPAT	OR	ON	2007/03/14 10:47
S11 2	0	S110 and spin and bake	USPAT	OR	ON	2007/03/14 11:04
S11 3	21488	(polymethyl adj methacrylate)	USPAT	OR	ON	2007/03/14 11:12
S11 4	26104	(polyacrylic adj acid)	USPAT	OR	ON	2007/03/14 11:12
S11 5	1590	(polymethyl adj acrylate)	USPAT	OR	ON	2007/03/14 11:12
S11 6	26104	polyacrylic adj acid	USPAT	OR	ON	2007/03/14 11:12
S11 7	45330	S113 or S114 or S115 or S116	USPAT	OR	ON	2007/03/14 11:12
S11 8	15	S110 and S117	USPAT	OR	ON	2007/03/14 11:12
S11 9	2	"6261721".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/14 13:52
S12 0	21488	(polymethyl adj methacrylate)	USPAT	OR	ON	2007/03/14 13:52
S12 1	26104	(polyacrylic adj acid)	USPAT	OR	ON	2007/03/14 13:52
S12 2	1590	(polymethyl adj acrylate)	USPAT	OR	ON	2007/03/14 13:52
S12 3	26104	polyacrylic adj acid	USPAT	OR	ON	2007/03/14 13:52
S12 4	45330	S120 or S121 or S122 or S123	USPAT	OR	ON	2007/03/14 13:52
S12 5	2	"6261721".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/14 13:52

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S12 6	1	S125 and S124	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/14 14:01
S12 7	2	"6190824".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/14 14:01